ABSTRACT

The present invention provides anovel hexaarylbiimidazole compound of the following formula (1):

$$\begin{array}{c|c}
R_1 & & \\
N & & \\
N & & \\
N & & \\
R_2 & & \\
R_2 & & \\
\end{array}$$

- wherein each R_1 represents a halogen, and each R_2 represents an optionally substituted C_{1-4} alkyl group. The hexaarylbiimidazole compound of the present invention is useful as a photoradical generator in photopolymerizable compositions used as resists and is characterized by low sublimating thermal decomposition products.
- The photopolymerizable compositions may be suitably used as resists or as color filters for color liquid crystal display elements, cameras and the like.